

ABSTRACT

Provided is a mask blank wherein, even when a defect is present on the main surface of a substrate of the mask blank, the defect can be made to not affect a transfer image formed by a transfer mask, such that the mask blank is deemed acceptable. This mask blank is provided with a thin film that is for transfer pattern formation and provided on the main surface of a translucent substrate, wherein a defect is present on the main surface of the translucent substrate, and the defect satisfies the relationship $L \leq 97.9 \times w^{-0.4}$, where w is the width as viewed from the main surface side, and L is the length from the main surface to the tip of the defect in a direction perpendicular to the main surface.